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(54) Title: DEVELOPABLE RESIST OVERLAYER COMPOSITION AS WELL AS METHOD FOR MANUFACTURING RESIST
OVERLAYER PATTERN AND RESIST PATTERN

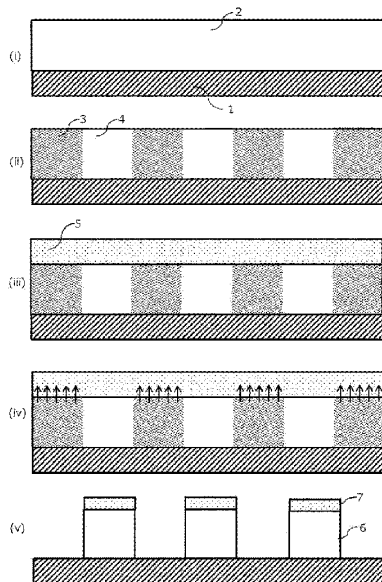


Figure 1

(57) Abstract: A developable resist overlayer composition as well as a method for
manufacturing a resist overlayer pattern and a resist pattern are provided.

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